**INFORMATION DISCLOSURE CITATION**

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ATTY DOCKET NO.

ITL1054US(P17790)

SERIAL NO.

10/695,103

APPLICANT(S):

Huey-Chiang Liou et al.

FILING DATE:

October 28, 2003

GROUP ART UNIT:

2823

**U.S. PATENT DOCUMENTS**

*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	AA						
	AB						
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						

**FOREIGN PATENT DOCUMENTS**

		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO
	AJ							
	AK							
	AL							
	AM							
	AN							
	AO							
	AP							

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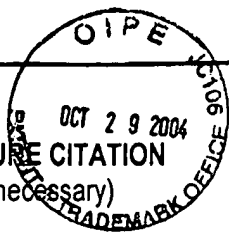
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